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(54) **SILICON BASED SUBSTRATE WITH ENVIRONMENTAL/THERMAL BARRIER LAYER**

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(58) **Field of Search** 427/450, 452, 427/453

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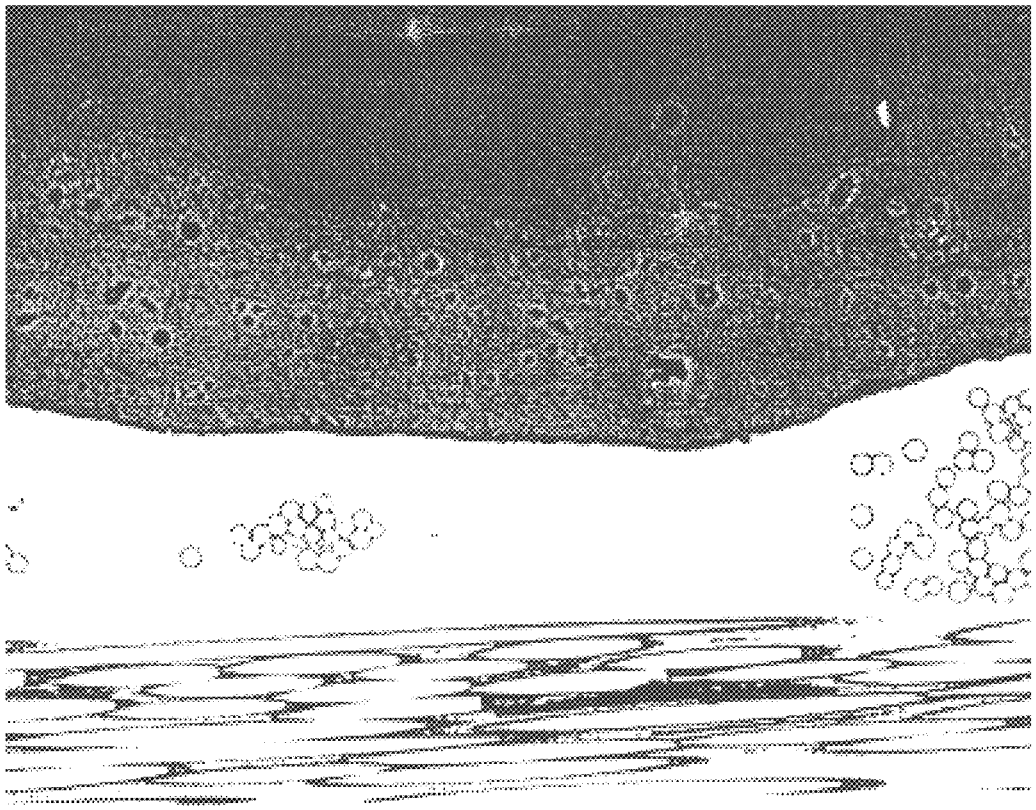
(57) **ABSTRACT**

A barrier layer for a silicon containing substrate which inhibits the formation of gaseous species of silicon when exposed to a high temperature aqueous environment comprises a barium-strontium alumino silicate.

28 Claims, 4 Drawing Sheets